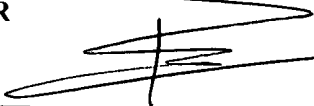


<b>INFORMATION DISCLOSURE STATEMENT</b>	<b>Atty. Docket No.:</b> 150.01180101	<b>Serial No.:</b> 10/032,049
	<b>Applicants:</b> Brian A. Vaartstra	<b>Confirmation No.:</b> 5131
	<b>Filing Date:</b> December 21, 2001	<b>Group:</b> 2814
Information Disclosure Statement mailed: _____, 2002		

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
TZ	4,992,137	02/12/91	Cathey, Jr. et al.			
TZ	5,254,217	10/19/93	Maniar et al.			
	5,380,401	01/10/95	Jones et al.			
	5,392,189	02/21/95	Fazan et al.			
	5,575,885	11/19/96	Hirabayashi et al.			
	5,692,950	12/02/97	Rutherford et al.			
	5,711,851	01/27/98	Blalock et al.			
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	5,976,928	11/02/99	Kirlin et al.			
	5,981,454	11/09/99	Small			
	5,989,988	11/23/99	Iinuma et al.			
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	6,143,191	11/07/00	Baum et al.			
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TZ	6,368,518 B1	04/09/02	Vaartstra			

<b>EXAMINER</b> 	<b>Date Considered</b> 11/26/02
*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

**INFORMATION  
DISCLOSURE  
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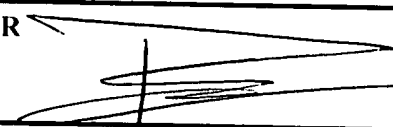
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
TL	6,395,194 B1	05/28/02	Russell et al.			

**FOREIGN PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
TL	WO 98/06541 ✓	02/19/98	PCT				
	WO 98/36045 ✓	08/20/98	PCT				
	WO 99/27581 ✓	06/03/99	PCT				
	WO 99/53532 ✓	10/21/99	PCT				
TL	WO 00/31794 ✓	06/02/00	PCT				

**OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)**

Examiner Initial	Document Description
TL	Canterford et al., "Chapter 9: Rhodium and Iridium," <i>Halides of the Transition Elements, Halides of the Second and Third Row Transition Metals</i> , John Wiley & Sons, New York, NY, 1968; pgs. 346-357, publication page, title page (14 pages total).
	DeOrnellas et al., "Challenges for Plasma Etch Integration of Ferroelectric Capacitors in FeRAM's and DRAM's," <i>Integrated Ferroelectrics</i> , 1997;17:395-402.
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	Ginzburg et al., <i>Analytical Chemistry of Platinum Metals</i> , John Wiley & Sons, New York, 1975, cover pg., and 14-15.
TL	Kim et al., "Chemical Dry Etching of Platinum Using Cl <sub>2</sub> /CO Gas Mixture," <i>Chem. Mater.</i> , 1998;10:3576-3582.

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TZ	Kwon et al., "Etching properties of Pt thin films by inductively coupled plasma," <i>J. Vac. Sci. Technol.</i> , 1998;A 16(5):2772-6.
TZ	Nakao, "Dissolution of Noble Metals in Halogen-Halide-Polar Organic Solvent Systems," <i>J. Chem. Soc., Chem. Commun.</i> , 1992 March 1; 5:426-7.
TZ	Wiberg, "Chapter XXX, No. 4: Chemical Properties," <i>Lehrbuch der Anorganischen Chemie</i> , Walter de Gruyter, Berlin, 1985, p. 1118 (Translation of First paragraph only).
TZ	Xu et al., "Chemical Vapor Deposition (CVD) of Iridium and Platinum Films and Gas-Phase Chemical Etching of Iridium Thin Films," <i>Mat. Res. Soc. Symp. Proc.</i> , 1999;541:129-139.

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